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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Complete if Known

Application Number	10/652,007
Filing Date	August 29, 2003
First Named Inventor	Sheldon Aronowitz
Group Art Unit	1765
Examiner Name	David M. Brunzman
Attorney Docket No.	/ 00-643/1D

Sheet 1 of 1

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code (if known)			
h		5,152,819		Blackwell et al.	10-06-1992	
h		5,879,649		Henderson et al.	03-09-1999	
h		6,020,458		Lee et al.	02-01-2000	
h		6,508,997		Choate et al.	01-21-2003	

Examiner signature		Date considered	2/18/05
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Received from <408 433 7480> at 10/21/03 6:04:27 PM [Eastern Daylight Time] TO THIS ADDRESS, SEND TO: Assistant Commissioner for Patents.

FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Docket No.	Serial No.
	00-643/1D	
	Applicants	
	Sheldon Aronowitz et al.	
Filing Date Herewith	Group Unknown	

U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
L	AA	5,874,367	2/23/99	Dobson	438	787	
L	AB	6,028,015	2/22/00	Wang et al.	438	789	3/29/99
L	AC	6,114,259	9/5/00	Sukharev et al.	438	789	7/27/99
L	AD	6,147,012	11/14/00	Sukharev et al.	438	787	11/12/99
L	AE	6,043,167	3/28/00	Lee et al.	438	789	10/10/97
L	AF	5,314,845	5/24/94	Lee et al.	437	238	2/2/90
L	AG	5,915,203	6/22/99	Sengupta et al.	438	669	6/10/97
L	AH	6,365,528	4/2/02	Sukharev et al.	438	778	6/7/00
L	AI	5,571,571	11/5/96	Musaka et al.	427	574	6/14/94
L	AJ	6,303,047	10/16/01	Aronowitz et al.	252	1	3/22/99
L	AK	6,511,925	1/28/03	Aronowitz et al.	438	788	10/19/01

Foreign Patent Documents							
							Translation
		Document Number	Date	Country	Class	Subclass	Yes No
	AL						
	AM						
	AN						
	AO						
	AP						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
L	AR	Bothra, S., et al., "Integration of 0.25 μ m Three and Five Level Interconnect System for High Performance ASIC", 1997 Proceedings Fourteenth International VMIC Conference, Santa Clara, CA, June 10-12, 1997, pp.43-48.
L	AS	Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silane and H ₂ O ₂ ", Semiconductor International, December 1994, pp. 85-88.
L	AT	McClatchie, S., et al., "Low Dielectric Constant Oxide Films Deposited Using CVD Techniques", 1998 Proceedings Fourth International DUMIC Conference, February 16-17, 1998, pp. 311-318.

Examiner	<i>[Signature]</i>	Date Considered	2/18/05
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.			

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					Filing Date Herewith		Group Unknown	

U.S. Patent Documents							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>r</i>	BA	6,066,574	5,23/00	You et al.	438	781	11/6/98
<i>a</i>	BB	6,051,477	4/18/00	Nam	438	404	10/22/96
<i>h</i>	BC	6,025,263	2/15/00	Tsai et al.	438	624	9/11/97
<i>a</i>	BD	5,939,763	8/17/99	Hao et al.	257	411	9/5/96
<i>h</i>	BE	5,864,172	1/26/99	Kapoor et al.	257	634	8/13/96
<i>h</i>	BF	5,688,724	11/18/97	Yoon et al.	437	235	12/23/94
<i>h</i>	BG	5,470,801	11/28/95	Kapoor et al.	437	238	6/28/93
<i>h</i>	BH	5,364,800	11/15/94	Joyner	437	28	6/24/93
<i>h</i>	BI	4,771,328	9/13/88	Malaviya et al.	357	49	11/24/86
<i>r</i>	BJ	3,652,331	3/28/72	Yamazaki	117	201	3/13/69
	BK						

Foreign Patent Documents							
							Translation
	Document Number	Date	Country	Class	Subclass	Yes	No
	BL						
	BM						
	BN						
	BO						
	BP						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
<i>a</i>	BR	Nguyen, S. et al., "Reaction Mechanisms of Plasma- and Thermal-Assisted Chemical Vapor Deposition of Tetraethylorthosilicate Oxide Films", <u>J. Electrochem. Soc.</u> , Vol. 137, No. 7, July, 1990, pp. 2209-2215.
<i>h</i>	BS	Peters, Laura, "Low-k Dielectrics: Will Spin-On or CVD Prevail?", <u>Semiconductor International</u> , Vol. 23, No. 6, June, 2000, pp. 108-110, 114, 116, 118, 122, and 124.
<i>h</i>	BT	Peters, Laura, "Pursuing the Perfect Low-k Dielectric", <u>Semiconductor International</u> , Vol. 21, No. 10, September, 1998, pp. 64-66, 68, 70, 72, and 74.

Examiner <i>gklyn</i>	Date Considered <i>2/18/05</i>
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(Use several sheets if necessary)

Applicants

Sheldon Aronowitz et al.

Filing Date
HerewithGroup
Unknown

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
g	CA	6,153,524	11/28/00	Henley et al.	438	691	7/28/98
h	CB	6,051,073	4/18/00	Chu et al.	118	723	6/3/98
h	CC	5,580,429	12/3/96	Chan et al.	204	192.38	6/7/95
a	CD	5,558,718	9/24/96	Leung	118	723E	4/8/94
v	CE	5,628,871	5/13/97	Shinagawa	438	514	6/24/94
h	CF	6,204,192	3/20/01	Zhao et al.	438	723	3/29/99
a	CG	6,232,658	5/15/01	Catabay et al.	257	701	6/30/99
n	CH	6,037,248	3/14/00	Ahn	438	619	6/13/97
h	CI	5,675,187	10/7/97	Numata et al.	257	758	5/16/96
h	CJ	5,559,367	9/24/96	Cohen et al.	257	77	7/12/94
c	CK	5,376,595	12/27/94	Zupancic et al.	501	12	8/28/92

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Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
c	CL	2000-267128	9/29/00	Japan	G02F	1/136	X-Abstract Only	
	CM							
	CN							
	CO							
	CP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

a	CR	Sugahara, Satoshi, et al., "Chemical Vapor Deposition of CF ₃ -Incorporated Silica Films for Interlayer Dielectric Application", 1999 Joint International Meeting, <u>Electrochemical Society Meeting Abstracts</u> , Vol. 99-2, 1999, Abstract No. 746.
v	CS	Koda, Seiichiro, et al., "A Study of Inhibition Effects for Silane Combustion by Additive Gases", <u>Combustion and Flame</u> , Vol. 73, No. 2, August, 1988, pp. 187-194.
	CT	

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HerewithGroup
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
A	DA	5,904,154	5/18/99	Chien et al.	134	1.2	7/24/97
a	DB	5,882,489	3/16/99	Bersin et al.	204	192.35	4/26/96
A	DC	5,858,879	1/12/99	Chao et al.	438	725	6/6/97
A	DD	3,012,861	12/12/61	Ling	23	223.5	1/15/60
u	DE	3,178,392	4/13/65	Kriner	260	46.5	4/9/62
a	DF	3,832,202	8/27/74	Ritchie	106	287	8/8/72
A	DG	3,920,865	11/18/75	Läufer et al.	427	220	4/6/72
A	DH	4,705,725	11/10/87	Glaich et al.	428	405	11/28/86
A	DI	5,194,333	3/16/93	Ohnaka et al.	428	405	12/18/90
A	DJ	5,874,745	2/23/99	Kuo	257	59	8/5/97
	DK						

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							Translation	
		Document Number	Date	Country	Class	Subclass	Yes	No
T	DL	DE 198 04 375 A1	7/1/99	Germany	H 01 L	21/312		X
a	DM	EP 0 706 216 A2	4/10/96	Europe	H 01 L	23/532	N/A	
u	DN	EP 0 949 663 A2	10/13/99	Europe	H 01 L	21/312	N/A	
A	DO	63003437	1/8/88	Japan	H 01 L	21/90	X-Abstract Only	
A	DP	WO 99/41423	8/19/99	PCT	C 23 C		N/A	

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	DR	
	DS	
	DT	

Examiner

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2/8/08

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